

## Amendments to the Claims

### Claims 1 and 2 (Canceled)

Claim 3 (Currently Amended) A substrate polishing apparatus comprising:

~~a polishing rotatable table having a polishing pad for polishing a semiconductor substrate;~~  
~~a polishing pad mounted on said polishing table for polishing a semiconductor substrate,~~  
~~said polishing pad having a through hole formed therein;~~

~~a light emission and reception device for emitting measurement light through said a~~  
~~through hole formed in said polishing pad to the said semiconductor substrate and receiving~~  
~~reflected light from the said semiconductor substrate so as to measure a film on the said~~  
~~semiconductor substrate, said light emission and reception device being disposed in said~~  
~~polishing table; and~~

~~a supply passage for supplying a fluid to a path of the said measurement light, said supply~~  
~~passage having an outlet portion detachably mounted on said polishing table; and~~  
~~wherein said supply passage has an outlet portion detachably mounted on said rotatable~~  
~~table~~

~~a protection cover mounted on said polishing table and fitted into said through hole when~~  
~~said polishing pad is attached to said polishing table.~~

### Claims 4-33 (Canceled)

Claim 34 (Previously Presented) A substrate polishing apparatus according to claim 3, wherein  
said outlet portion comprises a pipe unit which has a pipe piece.

Claim 35 (Previously Presented) A substrate polishing apparatus according to claim 34,  
wherein said pipe unit has a light-emitting optical fiber constituting said light emission and  
reception device.

**Claim 36 (Previously Presented)** A substrate polishing apparatus according to claim 34, wherein said pipe unit has a light-receiving optical fiber constituting said light emission and reception device.

**Claim 37 (Currently Amended)** A substrate polishing apparatus according to claim 3, wherein the said fluid comprises pure water.

**Claim 38 (Currently Amended)** A polishing apparatus comprising:

    a polishing table having a polishing pad for polishing a workpiece, said polishing pad having a hole;

    an optical measurement device disposed in said polishing table for emitting measurement light to the said workpiece through said hole and receiving reflected light from the said workpiece so as to measure a film on the said workpiece; and

    a supply passage disposed in said polishing table for supplying a fluid to a path of the said measurement light, said supply passage having an outlet portion detachably mounted on said polishing table; and

wherein said supply passage has an outlet portion detachably mounted on said polishing table

a protection cover mounted on said polishing table and fitted into said hole when said polishing pad is attached to said polishing table.

**Claim 39 (Previously Presented)** A polishing apparatus according to claim 38, wherein said outlet portion comprises a pipe unit which has a pipe piece.

**Claim 40 (Previously Presented)** A polishing apparatus according to claim 39, wherein said pipe unit has a light-emitting optical fiber constituting said optical measurement device.

**Claim 41 (Previously Presented)** A polishing apparatus according to claim 39, wherein said pipe unit has a light-receiving optical fiber constituting said optical measurement device.

Claim 42 (**Currently Amended**) A polishing apparatus according to claim 38, wherein the said fluid comprises pure water.

Claim 43 (**New**) A polishing apparatus according to claim 3, wherein said polishing table has a discharge passage disposed therein, and the polishing apparatus further comprises a pump connected to said discharge passage for compulsorily discharging the fluid in the path of the measurement light.

Claim 44 (**New**) A polishing apparatus according to claim 38, wherein said polishing table has a discharge passage disposed therein, and the polishing apparatus further comprises a pump connected to said discharge passage for compulsorily discharging the fluid in the path of the measurement light.

Claim 45 (**New**) A polishing apparatus according to claim 3, further comprising an outlet portion moving means for vertically moving said outlet portion.

Claim 46 (**New**) A polishing apparatus according to claim 38, further comprising an outlet portion moving means for vertically moving said outlet portion.